U.S. Patent Application No. 09/823,196

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE RECEIVED CENTRAL FAX CENTER AUG. 2 6 2004

In re United States Patent Application of:

Applicants:

Thomas H. Baum, et al.

Group Art Unit: 1621

Serial No:

09/945,831

Examiner: Na

Nazario Gonzalez,

Porfirio

Date Filed:

**September 18, 2001** 

LOUTIN

Confirmation No.: 8827

Title:

Source Reagent Compositions for CVD

Customer No.: 25559

Formation of Gate Dielectric Thin Films Using Amide

Precursors and Method of Using Same

## FACSIMILE TRANSMISSION CERTIFICATE

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Maggic Chappuis

August 26, 2004
Date of Transmission

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AMENDMENT RESPONDING TO FEBRUARY 26, 2004 OFFICE ACTION IN U.S. PATENT APPLICATION NO. 09/954,831 AND PETITION FOR EXTENSION OF TIME UNDER 37 C.F.R. § 1.136

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

This responds to the February 26, 2004 Office Action in the above-identified application. Please amend the application as set out in the following Section I (Amendment of the Claims). Remarks addressing the substance of the February 17, 2004 Office Action are set out in Section II (Remarks) hereof.